

ABSTRACT
FERROMAGNETIC SPUTTERING TARGET

5 Provided is a ferromagnetic sputtering target having a metal composition
comprising 20 mol% or less of Cr, 5 mol% or more of Pt, and the balance of Co,
wherein the target includes a metal base (A) and two different phases (B) and (C)
in the metal base (A), the phase (B) being a Co-Ru alloy phase containing 30
mol% or more of Ru, and the phase (C) being a metal or alloy phase primarily
10 composed of Co or a Co alloy. The present invention improves the leakage
magnetic flux to provide a ferromagnetic sputtering target that can perform stable
discharge with a magnetron sputtering device.